

Figure S1. The leakage current of the OTFTs based on various dielectric layer by applying the gate voltage from 1 to -5V.

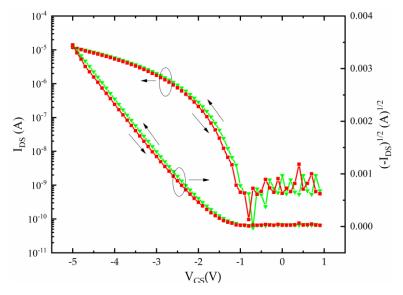


Figure S2. The hysteresis characteristic of OTFT device with improved sol–gel SiO_x/PVP dielectric layer.

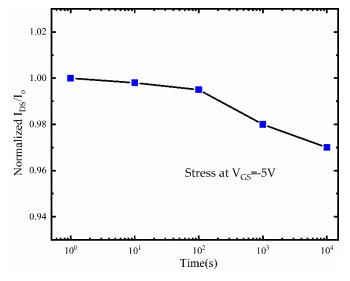


Figure S3. The normalized D/S current of OTFT device with improved Sol-gel SiO_x/PVP dielectric layer when constant bias stress $V_{GS} = -5$ V is applied for more than 3 h.